

REMARKS

Interview Summary

Applicants appreciate the Examiner's Interview granted on May 15 and June 21, 2006. Applicants discussed the novelty of an opaque insulating layer. An opaque insulating layer was not disclosed in Nagayama, et al. The Examiner has requested additional information regarding the opacity of OFPR 8000, the material used by Nagayama for an insulating layer. Applicants informed the Examiner that OFPR 8000 required a "masking layer" not required with the Applicants' opaque insulating layer.

Drawings

Applicants have corrected a typographical error in the drawings. The figure label "300" was replaced with the label "200." Additionally, the figure label "310" was replaced with "202" or "202a" where appropriate. The amendments to the drawings are supported in the "Brief Description of the Reference Numerals" on page 7 of the specification. Additionally, anodes 202a are described on page 8, lines 6-10. Specifically, "photoresists are provided on the conductive material 202 as masks such that a plurality of anode electrodes 202a of transparent conductive material of stripe shapes arranged in parallel are formed from the conductive material 202..." Figure labels 200, 202, and 202a are described in the specification.

Nagayama does not disclose "opaque insulating layer"

The Examiner has rejected claims 12-15, 17-23, and 25-26 as anticipated by Nagayama (US 5,701,055). Nagayama does not disclose an "opaque insulating layer." Because Nagayama is silent regarding the opacity of the insulating layer and Nagayama requires a masking layer, Nagayama does not anticipate the claims. Applicants kindly request the Examiner remove this rejection.

CONCLUSION

Applicants have addressed the typographical errors in the drawing and the Examiner's concerns regarding opacity of the Nagayama insulating layer. Applicants have specifically identified the advantages of the "opaque insulating layer" in contrast to the masking technique used by Nagayama.

In view of the above, each of the presently pending claims in this application is believed to be in immediate condition for allowance. Accordingly, the Examiner is respectfully requested to pass this application to issue. Applicants respectfully request the Examiner contact them if there are any questions or procedures that need to be addressed. No fees are believed to be due for this submission. However, should there be any additional fees required, please charge such additional fees to Deposit Account No. 50-3420, under Order No. 87141181-242001DV (MDB).

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Respectfully submitted,

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